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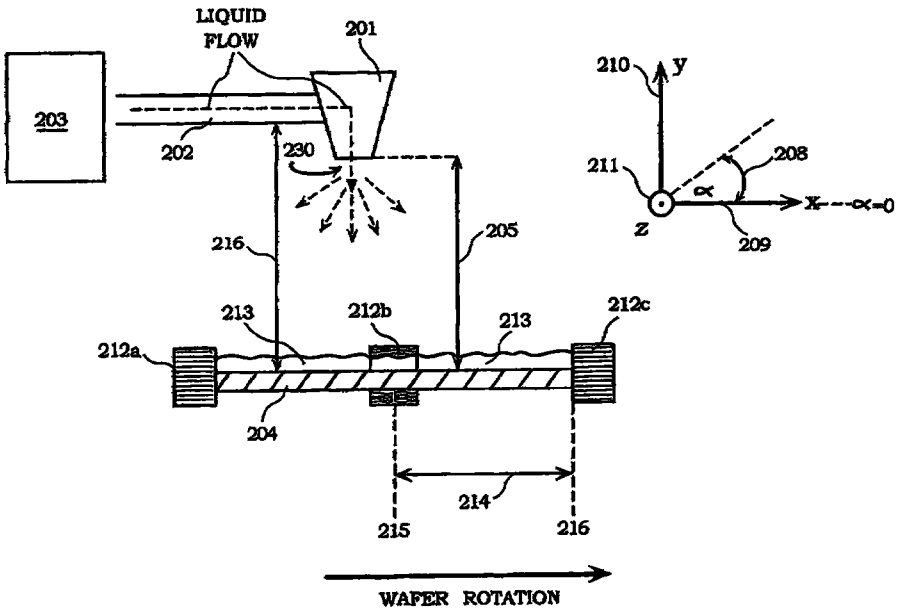
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(54) Title: HIGH RPM MEGASONIC CLEANING



(57) Abstract: A method that involves spraying a liquid agitated with a sonic wave at a megasonic frequency onto a substrate (204) from a nozzle (201) positioned over the substrate. Simultaneously, the substrate is spun above 300RPM while the nozzle is swept over the substrate. The substrate may be brushed in a brush station before agitating the liquid with the sonic wave. An apparatus having an arm (202) in fluid communication with a nozzle that has an angular position θ greater than 0°. Also, there is a substrate spinner (212) positioned below the nozzle.

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